

12. (Amended) The substrate cleaning system according to Claim 10 [or 11], wherein the chamber body 80 comprises a chemical supply section 91 for supplying cleaning solution onto a substrate surface supported by the substrate rotating unit 81, an inert gas supply section 92 for supplying inert gas so as to discharge and exchange cleaning solution, and a drain section provided in each processing bath so as to drain cleaning solution or inert gas in each processing bath.



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